

[illegible]

Abstract of Disclosure

A method of correcting a mask layout is provided. The mask layout includes a plurality of element patterns. An inspection program is executed to classify the element patterns of the mask layout into a plurality of element pattern types according to a pattern density of the element patterns. Following this, each of the element pattern types is corrected so as to prevent a plasma micro-loading effect.

Figures

Figure 1: A line graph showing the relationship between the number of hours spent studying and the score on a test. The x-axis represents 'Hours Studied' (0 to 10) and the y-axis represents 'Test Score' (0 to 100). The data points are as follows:

Hours Studied	Test Score
0	50
1	55
2	60
3	65
4	70
5	75
6	80
7	85
8	90
9	95
10	100

The graph shows a positive linear relationship, indicating that as the number of hours spent studying increases, the test score also increases proportionally.